

P27374.A06

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicants : Dureseti CHIDAMBARRAO, et al. Group Art Unit: 2814

Appln. No. : 10/605,108 Examiner: PHAM, Long

Filed : September 9, 2003 Confirmation No. 2107

For : METHOD FOR REDUCED N+ DIFFUSION IN STRAINED SI
ON SI/GE SUBSTRATE

AMENDMENT UNDER 37 C.F.R. 1.111

Commissioner for Patents
U.S. Patent and Trademark Office
Customer Window, Mail Stop Amendment
Randolph Building
401 Dulany Street
Alexandria, VA 22314
Sir:

Responsive to the non-final Official Action of December 28, 2005,
reconsideration and withdrawal of the rejections made therein are respectfully
requested, in view of the following amendments and remarks.

Amendments to the claims begin on page 2; and
Remarks begin on page 7.

Inasmuch as the Official Action sets a three-month shortened statutory period
which expires March 28, 2006, this Amendment is being timely filed and no extension of
time is believed necessary. However, if an extension is deemed by the Patent and
Trademark Office to be necessary, the same is hereby requested and the Patent and
Trademark Office is hereby authorized to charge any necessary fees in connection
therewith or any fees necessary to preserve the pendency of this application to deposit
account No. 09-0458.